

Title (en)

DEVICE MANUFACTURE INVOLVING PATTERN DELINEATION IN THIN LAYERS.

Title (de)

VERFAHREN ZUR HERSTELLUNG EINER ANORDNUNG UNTER VERWENDUNG VON STREIFENMUSTERN IN DÜNNSCHICHTEN.

Title (fr)

FABRICATION D'UN DISPOSITIF COMPORTANT UNE TRACE DE MODELES DANS DES COUCHES FINES.

Publication

**EP 0035529 A4 19820216 (EN)**

Application

**EP 80901737 A 19810309**

Priority

US 7140879 A 19790830

Abstract (en)

[origin: WO8100646A1] Etch procedures are monitored electrically by initiation of current flow upon baring of conducting surface (19) to etching fluid (11). Procedures include photoresist development in which current flow is through the usual aqueous ionic developing solution. In an exemplary use, a specifically designed monitoring wafer (10) serves for detection of end point for a batch of wafers undergoing processing.

IPC 1-7

**H01L 21/306**

IPC 8 full level

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CPC (source: EP)

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